

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	7	tipro	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/04 12:13
S2	799	(mask or masking) and lithography and ligand	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 14:28
S3	297	titanium and S2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/24 08:40
S4	70	isomer and S3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/24 08:50
S5	2	("6348239").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/01/24 08:50
S6	1	("5534312").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/01/24 08:53
S7	25	("5534312").URPN.	USPAT	OR	ON	2005/01/24 08:55
S8	15	("4770590" "5140366" "5178989" "5272099" "5292558" "5436176" "5534312" "5627087" "5652166" "5716758" "5935762" "5989759" "6072207" "6307087" "6387012").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/01/24 08:59
S9	154	(mask or masking) and lithography and ligand and nano	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/24 12:21
S10	48	titanium adj diisopropoxide and acetoacetate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/24 12:49

S11	1	("5534312").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/02/03 14:23
S12	29	("5534312").URPN.	USPAT	OR	ON	2006/02/03 14:28
S13	6933	remove adj exposed	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/04 12:50
S14	16	((mask or masking) and lithography and ligand) and S13	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 14:34
S15	10112	positive adj resist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 14:34
S16	158258	ligand	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 14:34
S17	173	S15 and S16	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 14:34
S18	71267	remove near4 exposed or removed near4 exposed or removing near4 expose or removing near4 exposure or remove near4 exposure or removed near4 exposure	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 14:43
S19	2386	S15 and S18	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 14:43
S20	66	S16 and S19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 14:43

S21	7559	protic adj solvent	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:00
S22	762909	exposure	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:01
S23	1235	S21 and S22	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:01
S24	4384166	metal	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:01
S25	4454808	metal or ligand	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:01
S26	1093	S23 and S25	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:01
S27	3981786	light or exposure or exposing	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:01
S28	1093	S26 and S27	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:02

S29	613103	mask or masking	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:02
S30	184	S28 and S29	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:12
S31	84	fury.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:20
S32	1790	maloney.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:20
S33	271271	precursor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:20
S34	4384166	metal	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:20
S35	149533	S33 and S34	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:20
S36	25	S32 and S35	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:23

S37	959	svendsen.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:24
S38	41	S35 and S37	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:30
S39	6	hohertz.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:34
S40	10	bravo-vasquez.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:36
S41	203	ekc.as.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:36
S42	1	S13 and S41	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/03 15:36
S43	144	pmod or photochemical adj metal adj organic adj deposition	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/04 12:13
S44	6933	remove adj exposed	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/04 12:50

S45	4896	mask and S44	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/04 12:50
S46	429	precursor and S45	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/04 12:50